

Atty. Dkt. No. 039153-0298 (F0785)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Calvin T. Gabriel et al.

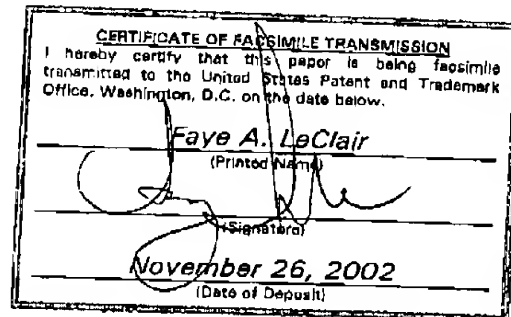
Title: SELECTIVE PHOTORESIST
HARDENING TO FACILITATE
LATERAL TRIMMING

Appl. No.: 09/819,343

Filing Date: 03/28/2001

Examiner: Sagar, K.

Art Unit: 1756

**AMENDMENT**Commissioner for Patents
Box NON-FEE AMENDMENT
Washington, D.C. 20231

Sir:

This communication is responsive to the Office Action dated August 27, 2002, concerning the above-referenced patent application.

Please amend the application as follows:

In the Specification:

Please replace paragraph number [0001] with the following paragraph. The changes are shown explicitly in the attached "Marked Up Version Showing Changes Made."

[0001] The present application is related to U.S. Application No. 09/819,692 (Atty. Dkt. No. 39153/404) by Okoroanyanwu et al., entitled "Process for Preventing Deformation of Patterned Photoresist Features by Electron Beam Stabilization;" U.S. Application No. 09/820,143 (Atty. Dkt. No. 39153/405) by Okoroanyanwu et al., entitled "Improving SEM Inspection and Analysis of Patterned Photoresist Features;" U.S. Application No. 09/819,344 (Atty. Dkt. No. 39153/406) by Okoroanyanwu et al.,

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